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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
09/923,725	08/06/2001	Gregory J. Goldspring	LAM2P267A	LAM2P267A 1734	
25920	7590 09/20/2004		EXAM	EXAMINER	
MARTINE & PENILLA, LLP			AHMED, SHAMIM		
710 LAKEWA SUITE 170	AY DRIVE		ART UNIT	PAPER NUMBER	
SUNNYVALI	E, CA 94085		1765		
			DATE MAILED: 09/20/2004		

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Applicatio	n No.	Applicant(s)	9
	09/923,72	5	GOLDSPRING ET AL.	
Office Action Summary	Examiner		Art Unit	
	Shamim A	hmed	1765	
The MAILING DATE of this communic	cation appears on the	cover sheet with the	correspondence addres	ss
A SHORTENED STATUTORY PERIOD FOTHE MAILING DATE OF THIS COMMUNION.  Extensions of time may be available under the provisions of after SIX (6) MONTHS from the mailing date of this communified the period for reply specified above is less than thirty (30).  If NO period for reply is specified above, the maximum stathes a failure to reply within the set or extended period for reply within the set or extended period for reply wany reply received by the Office later than three months after the patient term adjustment. See 37 CFR 1.704(b).	CATION.  of 37 CFR 1.136(a). In no ever  unication.  of days, a reply within the statul  utory period will apply and will  vill, by statule, cause the appli	nt, however, may a reply be to cory minimum of thirty (30) da expire SIX (6) MONTHS from cation to become ABANDON	timely filed  ays will be considered timely.  m the mailing date of this commu	inication.
Status				
<ol> <li>Responsive to communication(s) filed</li> <li>This action is FINAL.</li> <li>Since this application is in condition for closed in accordance with the practice</li> </ol>	b) This action is no or allowance except f	or formal matters, p		erits is
Disposition of Claims				
4) ☐ Claim(s) 1-3 and 16-19 is/are pending 4a) Of the above claim(s) is/are 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-3 and 16-19 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restrictions.	e withdrawn from con			
Application Papers				
9) The specification is objected to by the 10) The drawing(s) filed on is/are:  Applicant may not request that any object Replacement drawing sheet(s) including to 11) The oath or declaration is objected to	a) accepted or b) tion to the drawing(s) be the correction is required	held in abeyance. Sed if the drawing(s) is of	ee 37 CFR 1.85(a). bjected to. See 37 CFR 1.	
Priority under 35 U.S.C. § 119				
12) Acknowledgment is made of a claim for a) All b) Some * c) None of:  1. Certified copies of the priority d  2. Certified copies of the priority d  3. Copies of the certified copies of application from the Internation.  * See the attached detailed Office action	ocuments have been ocuments have been f the priority documer al Bureau (PCT Rule	received. received in Applicate ts have been received 17.2(a)).	tion No ved in this National Stag	ge
Attachment(s)  1) Notice of References Cited (PTO-892)  2) Notice of Draftsperson's Patent Drawing Review (PTO-33) Information Disclosure Statement(s) (PTO-1449 or Paper No(s)/Mail Date  5. Patent and Trademark Office TOL-326 (Rev. 1-04)	TO/SB/08)	6) Other:		,

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#### **DETAILED ACTION**

## Response to Arguments

The amendment filed on 8/3/04 is sufficient to overcome the 112 second,
 paragraph rejection of the previous office action but the claim 19 is still rejected under
 second paragraph.

The pending claims are rejected as below:

### Claim Rejections - 35 USC § 112

2. The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

- 3. Claim 19 is rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.
- 4. Claim 19 recites the limitation "The apparatus of claim 1" in line 1. There is insufficient antecedent basis for this limitation in the claim.

The phrase "The apparatus" should have been meant "The product".

## Claim Rejections - 35 USC § 102

5. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

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6. Claims 1-3 and 16-18 are rejected under 35 U.S.C. 102(e) as being anticipated by Garaza et al (6,081,659) as evidenced by Rahman et al (5,521,052).

Garaza et al disclose a simulation process, wherein a product comprises a support layer of a semiconductor substrate (160), which resembles the claimed first layer, upon which a second layer of liquid photoresist composition layer (162), which is composed of a mixture of multiple material such as solvent and photoresist material, which second layer is formed on the support layer and the product is capable of simulating (col.7, lines 1-4 and lines 30-45).

Garaza et al inherently teach that the photoresist material includes metal ions such as copper, as evidenced by Rahman et al (col.1, lines 10-22 and col.3, lines 8-12).

Therefore, Garaza et al inherently teach that the generation of a byproduct comprising copper from the photoresist composition during the etching process using the photoresist material layer as a mask.

As to claim 16, Garaza et al as evidenced by Rahman et al teach that the photoresist or the novolak resin composition includes three of more materials (col.3, lines 8-10 of Rahman et al).

As to claim 17, since the second layer composition is exactly same as the instant invention, the claimed range of the etching time is an inherent property of the composition layer.

As to claim 18, Garaza et al teach that the photoresist is baked on the support layer (col.7, lines 47-52).

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# Claim Rejections - 35 USC § 103

- 7. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 8. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).
- 9. Claim 19 is rejected under 35 U.S.C. 103(a) as being unpatentable over Garaza et al (6,081,659) as evidenced by Rahman et al (5,521,052).

Garaza et al as evidenced by Rahman et al discussed above in the paragraph 6 but fail to explicitly teach that the ratio of the multiple materials in the mixture corresponds to an exposed area on the standard wafer being simulated.

Garaza et al teach that the photoresist is exposed to produce a pattern on the semiconductor substrate (col.8, lines 32-39).

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So, it would have been obvious that the ratio of the multiple materials in the mixture corresponds to an exposed area on the wafer to be simulated because the ratio of the photoresist composition is maintained in such that the composition having an extreme low level of metal ions as taught by Rahman et al.

#### Conclusion

10. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Milor et al (5,886,909) disclose a process of inspecting defect during the wafer simulation process.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Shamim Ahmed whose telephone number is (571) 272-1457. The examiner can normally be reached on M-Thu (7:00-5:30) Every Friday Off.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine G Norton can be reached on (571) 272-1465. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Shamim Ahmed Examiner Art Unit 1765

SA September 19, 2004